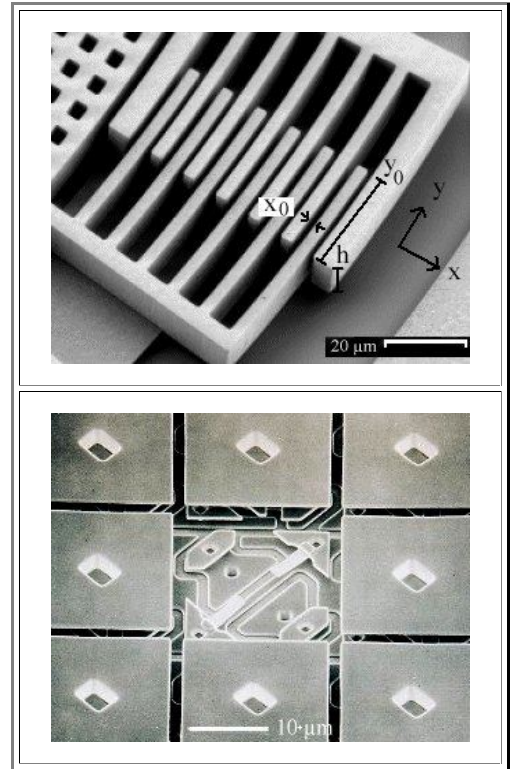


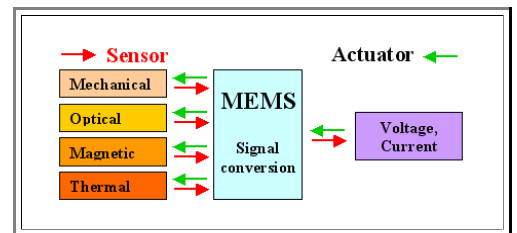
7.3 Summary

7.3.1 Summary to 7: MEMS

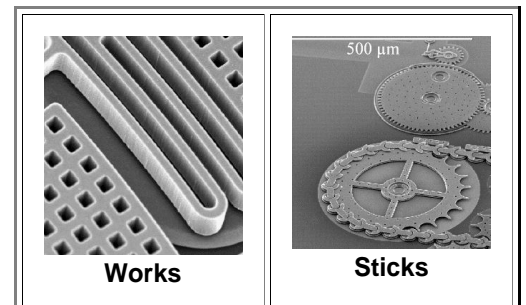
- MEMS are "Micro Electro Mechanical Systems" including also micro optics, micro fluidics and generally meaning micro systems.
- MEMS uses Si substrates and technologies because "it is there and cheap" for the non-electronic part *and* because electronic components can be integrated on the same chip.
- Examples of high-volume MEMS products are
 - (Pressure) sensors.
 - Accelerometers.
 - Gyros
 - "Beamer" chips (DLP)
- More products are to come; MEMS is an *emerging* and often an *enabling* technology
- Gyros are particular complex MEMS sensor products with a huge range of applications.
 - There must be a physical principle behind the sensor design; different approaches can be used.
 - One approach uses the **Coriolis force** causing detectable additional vibrations in an oscillator with two degrees of freedom if some rotation is experienced.



- Many MEMS devices are either sensors or actuators.
 - Looking only at mechanical MEMS, there is a need to couple mechanical movements to electrical signals and vice versa.
 - Ways to do this include.
 - Capacitive coupling
 - Piezoelectric and piezoresistive coupling.
 - Thermal coupling (expansion, resistivity changes).
 - Magnetic coupling.
 - Optical coupling.
 - There is no "ideal" coupling; all methods suffer from certain problems.



- MEMS uses all of "known" Si technology and has some specifics of its own.
 - Making cantilevers and membranes necessitates making "large" cavities.
 - Staying absolutely planar and stress-free is essential
 - Packaging can be far more demanding than for chips (e.g. transparent tops for OMEMS, keeping defined pressures for > 10 a in gyros).
- The **bane** of MEMS is **stiction**.
 - If you can't lubricate, it will stick sooner or later. Never bring moving parts in contact!
 - MEMS design therefore cannot just miniaturize existing mechanical designs; it must look for new approaches.



- MEMS employs some special processes and materials; they are the drivers of progress

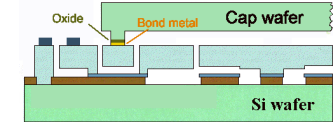
- Anisotropic chemical etching
- High-rate plasma etching ("Bosch process")
- Chemical-mechanical polishing
- Sacrificial layers and removal (including chemical etching with "vapors")
- Wafer bonding; in particular for packaging.

Making "large" cavities and extremely deep "holes"

Planarization

Free-standing structures

Process integration looks simple if compared to an advanced **CMOS** process, but is actually rather involved due to the special processes needed and quality requirements



Exercise 7.3-1

All Questions to 7.